DBs	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM TDB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM TDB	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT;
Search Text	(Trench with MOSFET) and implant\$5	S1 and (epitaxial with silicon)	trench and (NPN with transistor)	S3 and S4
Hits	1877	535	2103	10
Type	BRS	BRS	BRS	BRS

ന

4

	Туре	Hits	Search Text	DBs
₂	BRS	9	"5763902"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT:
				IBM_TDB
				US-PGPUB;
ဖ	BRS	141	(form with trench) with after EPO; JPO;	USPAI; USUCK; EPO; JPO;
			wicii (iiipiaiiceo wicii iayei)	DERWENT;
				IBM_TDB
				US-PGPUB;
				USPAT; USOCR;
7	BRS	5	S3 and S7	EPO; JPO;
				DERWENT;
				IBM_TDB
				US-PGPUB;
			7+; 1 (a); b)	USPAT; USOCR;
ထ	BRS	188	Commines water regarding water	EPO; JPO;
		·		DERWENT;
				IBM_TDB

	Type	Hits	Search Text	DBs
_	Ç	L		US-PGPUB; USPAT; USOCR;
_	BRS	4 b	S4 and trench	EPO; JPO; DERWENT; IBM_TDB
				US-PGPUB; USPAT; USOCR;
0	BRS	229	transistor)	EPO; JPO; DERWENT;
			•	IBM_TDB
				US-PGPUB;
,	(USPAT; USOCR;
H	BRS	0	S10 and S11	EPO; JPO; DERWENT;
				IBM TDB
				US-PGPUB;
			(forming with trench) with	USPAT; USOCR;
Ŋ	BRS	166	after with (forming with	EPO; JPO;
			implant\$5 with layer)	DERWENT;
				IBM TDB

	Туре	Hits	Search Text	DBs	
13	BRS	4161	257/327,330,341.ccls. or 438/270,302,514,519,527,542,5US-PGPUB; 48.ccls.	US-PGPUB;	USPAT
14	BRS	3344	S13 and implant\$5	US-PGPUB;	USPAT
15	BRS	1718	S14 and epitax\$6	US-PGPUB;	USPAT
16	BRS	390	S15 and channel and drift	US-PGPUB;	USPAT
17	BRS	350	(channel and drift) with implant\$5	US-PGPUB;	USPAT
18	BRS	1287	(epitaxial with silicon) with doping	with US-PGPUB;	USPAT
19	BRS	756	S18 and channel	US-PGPUB;	USPAT